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UNKNOWN

**U.S. PATENT DOCUMENTS**

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
V	U.S. Patent 3,432,401	3/11/69	C. Tcherkawsky	203	15	1002 U.S. PRO 10/04/29/31 01/08/02
V	U.S. Patent 3,433,831	3/18/69	A. Yomiyama et al.	260	526	
V	U.S. Patent 3,666,632	5/30/72	M. Honda et al.	203	56	
V	U.S. Patent 3,859,175	1/17/75	T. Ohrui et al.	203	46	
V	U.S. Patent 3,968,153	7/6/76	T. Ohrui et al.	260	526N	
V	U.S. Patent 4,142,058	2/27/79	H. Matsumura et al.	562	600	
V	U.S. Patent 4,166,774	9/4/79	D.R. Wagner	203	82	
V	U.S. Patent 4,554,054	11/19/85	R.W. Coyle	203	15	
V	U.S. Patent 5,154,800	10/13/92	L. Berg	203	15	
V	U.S. Patent 5,315,037	5/24/94	K. Sakamoto et al.	562	545	
V	U.S. Patent 5,759,358	6/2/98	W. Bauer, Jr. et al.	203	38	

**FOREIGN PATENT DOCUMENTS**

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
V	Jap.Pat. Abs. JP5215390	12/21/77	Japan	C07C	57/04	✓	
V	EPO Pub. 0551111 A1	7/14/93	EPO	C07C	57/07	✓	
V	British Spec. 1,120,284	7/17/68	Great Britain	C07C	57/04	✓	
V	British Spec. 1,290,725	9/27/72	Great Britian	C07C	57/04	✓	
V	Brit. Appln.GB2001315A	1/31/79	Great Britain	C07C	69/54	✓	

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

V Kirk-Othmer, Encyclopedia of Chemical Technology, Third Edition, Volume 1, John Wiley & Sons, pp. 339-341

EXAMINER

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DATE CONSIDERED

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